



Atty. Dkt. No. 025311-0105

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ichiro OKABE et al.
Title: METHOD OF FORMING A FINE
PATTERN, AND METHOD OF
MANUFACTURING A
SEMICONDUCTOR DEVICE, AND
A SEMICONDUCTOR DEVICE
HAVING A FINE PATTERN

Appl. No.: 09/597,161

Filing Date: 06/20/2000

Examiner: Jose R. Diaz

Art Unit: 2815

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AMENDMENT WITH RCE

Commissioner for Patents
PO Box 1450
Alexandria, Virginia 22313-1450

Sir:

Prior to examination of the present Request for Continued Examination (RCE) on the merits, Applicants respectfully request that the above-identified prior application be amended as follows:

The amendments presented below are in compliance with the revised amendment format permitted in the Notice from the Office of Patent Legal Administration of the U.S. Patent and Trademark Office dated February 10, 2003, and published at 1267 OG 106 on February 25, 2003. Thus, the provisions of 37 CFR 1.121(a), (b), (c) and (d) are waived for amendments made in this application to the claims, specification, and drawings.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this document.

Remarks/Arguments begin on page 4 of this document.